

10/7/1,222

IN THE SPECIFICATION:

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Please amend the paragraph beginning on Page ⁴ 5, line ⁴ 1 to read as follows:

--The preferred embodiment of the invention applies to step-and-repeat or step-and-scan photolithography tools such as tool 10 shown in Figure 1. Photolithography tool 10 includes laser interferometer 12, which controls wafer stage 14. Tool 10 also includes alignment systems 16a, 16c, exposure apparatus 17 and computer 18 to analyze alignment data. A substrate, such as silicon wafer 20, coated with photosensitive layer 22 is located on wafer state 14.--